## Photochemical Reactions of Spiro[benzo[b]thiophene-2(3H), 1'-cyclopropan]-3-ones

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**Synopsis.** The photolysis of spiro[benzo[b]thiophene-2(3H),1'-cyclopropan]-3-one 1,1-dioxide (1) in benzene afforded 2-biphenylyl cyclopropyl ketone with extrusion of sulfur dioxide, whereas the irradiation of 1 in toluene or p-xylene formed photoreduced dimer and bibenzyl or 4,4'-dimethylbibenzyl, respectively. The photolysis of spiro-[benzo[b]thiophene-2(3H),1'-cyclopropan]-3-one in benzene afforded the valence isomer 2,3-dihydro[1]benzothieno[3,2-b]-furan.

In recent years, considerable attention has been focused on the photochemistry of five-membered heterocyclic ring systems.1) We reported that the photochemical reactions of 2-aryl-1,2-benzisothiazol-3(2H)-ones in benzene give dibenzo [b,f][1,4] thiazepin-10(11H)ones,2) whereas the photolyses of 2-substituted 1,2benzisothiazol-3(2H)-one 1,1-dioxides in benzene give N-substituted o-phenylbenzamides with extrusion of sulfur dioxide.<sup>3)</sup> In our systematic investigations of photochemical reactions of benzisothiazoles and their analogues, we wish to report here the photochemical behavior of spiro[benzo[b]thiophene-2(3H),1'-cyclopropan - 3-one 1, 1-dioxide (1) and spiro[benzo[b]-thiophene-2(3H), 1'-cyclopropan]-3-one (2). These are expected to be photoreduced at the carbonyl group and to break their bonds at spiro carbon-sulfur atom or at the highly-strained three membered ring.

When a solution containing of 1 in benzene was irradiated under argon with light of wavelength >280 nm, an extremely clean conversion to a single photoproduct occurred. This product was deduced to be 2-biphenylyl cyclopropyl ketone (3) on the basis of its straightforward spectral properties (see experimental section). The reaction is quite similar to the photoreactions of 2-substituted 1,2-benzisothiazol-3(2H)-one 1,1-dioxides in benzene,3 and hence the reaction could be accounted for by a homolytic process via radical intermediates 4, 5, and 6, as shown in Scheme 1.

Meanwhile, when 1 was irradiated in toluene or p-xylene photoreduced dimer, 3,3"-bi[spiro[benzo[b]-thiophene-2(3H),1'-cyclopropane]]3,3"-diol 1,1,1",1"-tetraoxide (7) was formed with bibenzyl or 4,4'-dimethylbibenzyl, respectively, in good yield. No detectable quantities of such photoreduced alcohol as spiro-

[benzo[b]thiophene-2(3H), 1'-cyclopropan]-3-ol 1,1-dioxide (**8**) could be observed in the reaction mixture. The photoreaction of **1** in these solvents suggests that **1** in the photoexcited state abstracts the hydrogen atom from the methyl group of toluene or p-xylene to give radical **9** and benzyl (or p-methylbenzyl) radical (**10**) faster than a homolytic cleavage to **4** occurs. The absence of the alcohol **8** suggests that radical **9** has no ability to abstract the hydrogen atom from the methyl group of toluene or p-xylene and survive until a coupling reaction occurs to give dimer **7** (Scheme 2).

The photolysis of  $\mathbf{1}$  was also carried out in 2-propanol and the photoreduced dimer  $\mathbf{7}$  and pinacol were obtained. The reaction mechanism will be similar to the photolysis in toluene or p-xylene, involving the abstraction of the tertiary hydrogen from 2-propanol by  $\mathbf{1}$  in the photoexcited state.

The photoreaction of 1 behaved in quite different manners in benzene, and in toluene, *p*-xylene, or 2-propanol. 1 in the photoexcited state abstracts a hydrogen when the solvents are hydrogen donating, whereas in benzene 1 cleaves the C-S bond homolytically, affording radical intermediates 4 and 5. The photoreaction of 2-substituted 1,2-benzisothiazol-3(2*H*)-ones in benzene or 2-propanol, however, always included the extrusion of sulfur dioxide.<sup>3)</sup> It is also noteworthy that 7 is the sole photoreduced product and no formation of any product like 8 is observed in the photolysis of 1, in contrast to the reported photoreactions of phthalimides.<sup>4)</sup>

The photoreaction of **2** in benzene afforded 2,3-dihydro[1]benzothieno[3,2-*b*]furan (**11**) as the only isolable product. The reaction mechanism will be accounted for by the homolytic reaction shown in Scheme 3.

In this case, the reaction seems to proceed *via* the homolytic cleavage of the strained cyclopropane ring affording radical 12 and the following ring construction to give 11. The photolysis of 2 in toluene

or p-xylene did not form any isolable product in spite of the starting material was consumed.

## **Experimental**

Measurements. Melting points are uncorrected. IR and UV spectra were determined on a Hitachi EPI-G2 and a Hitachi 220A spectrophotometer. The proton magnetic spectra were recorded at 60 MHz by using a Hitachi R-20B spectrometer with TMS as an internal standard in CDCl<sub>3</sub>. Mass spectra were determined with a JMS-DX300 high resolution mass spectrometer. Elemental analyses were carried out by using a Perkin-Elmer 240 elemental analyzer.

Spiro[benzo[b]thiophene-2(3H),1'-cyclopropan]-3-one (2) was prepared from o-mercaptobenzoic acid (15.4g) and  $\alpha$ -bromo- $\gamma$ -butyrolactone (20.6g) according to the method described in the literature: 5 yield 10.5 g (65%) as colorless prisms form hexane-dichloromethane, mp 69-70°C (lit, mp 70°C).6 IR (KBr) 1680, 1590, 1450, 1320, 1080, 980, and 740 cm<sup>-1</sup>; NMR (CDCl<sub>3</sub>) δ 1.3-1.9 (4H, m) and 7.2—7.9 ppm (4H, m); UV (EtOH) 367 ( $\varepsilon$ =2.67×10<sup>3</sup>), 350  $(2.60\times10^3)$ , 267  $(5.50\times10^3)$ , 258  $(6.58\times10^3)$ , 237  $(3.36\times10^4)$ , and 208 nm  $(1.29\times10^5)$ . Spiro[benzo[b]thiophene-2(3H),1'cyclopropan]-3-one 1,1-dioxide (1) was prepared by the oxidation of 2 (5.2g) with 13.7g of perbenzoic acid in dichloromethane at 0°C: yield 5.6 g (91%) as colorless prisms from hexane-dichloromethane, mp 198-199°C (lit, mp 202°C).6) IR (KBr) 1720, 1590, 1460, 1315, 1300, 1155, and 990 cm<sup>-1</sup>; NMR (CDCl<sub>3</sub>)  $\delta$  1.30—2.00 (4H, m) and 7.40—8.10 ppm (4H, m); UV (MeOH) 292 ( $\varepsilon$ =6.55×10<sup>2</sup>), 283 (7.74×10<sup>2</sup>), 246  $(9.64 \times 10^3)$ , and  $210 \,\mathrm{nm} \ (3.35 \times 10^4)$ .

Photolysis of 1 in Benzene. A solution containing 200 mg of 1 in 220 cm<sup>3</sup> of benzene was irradiated under argon with a 450W medium-pressure mercury lamp (Hanovia) through a Corex filter sleeve for 8 h. Removal of the solvent under reduced pressure left a pale-yellow oil which was subjected to the chromatography on silica gel, using benzene as the eluent. 2-Biphenylyl cyclopropyl ketone (3) was isolated (130 mg, 86%)<sup>7)</sup> with 58 mg of unreacted starting material 1. The structure of 3 was assigned based on the following data: mp 81-82°C (from hexane); IR (KBr) 3020, 1670, 1595, 1450, 1435, 1280, 1040, and 990 cm<sup>-1</sup>; NMR (CDCl<sub>3</sub>)  $\delta$  0.50—0.72 (2H, m), 1.00—1.16 (2H, m), 1.64—1.88 (1H, m), 7.56 (5H, s), and 7.48—7.78 ppm (4H, m); Mass (20 eV) m/z 222 (M+), 194. 165, 153, 69, and 41. Found: C, 86.39; H, 6.23%. Calcd for C<sub>16</sub>H<sub>14</sub>O: C, 86.45; H, 6.35%.

Photolysis of 1 in Toluene. A solution containing 200 mg of 1 in 220 cm<sup>3</sup> of toluene was irradiated under argon through a Pyrex filter sleeve for 18 h. After removal of the

solvent, the photolysate was subjected to the chromatography on silica gel using a 2:1 hexane–ether mixture as the eluent to give bibenzyl (62 mg, 71%) and 7 (140 mg, 70%). The structure of bibenzyl was verified by comparison with an authentic sample, and that of 7 was identified on the basis of the following data: mp 276°C (decomp); IR (KBr) 3450, 3030, 1600, 1495, 1455, 1290, 1180, 1165, 1155, 1120, 1100, 1060, 1050, and 980 cm<sup>-1</sup>; NMR (CD<sub>3</sub>SOCD<sub>3</sub>)  $\delta$  0.91—1.6 (4H, m), 6.8—8.2 ppm (4H, m); Mass m/z 418 (M+), 362, 314, 209, 152, 136, 104, and 76. Found: m/z 209.02719. Calcd for C<sub>10</sub>H<sub>9</sub>O<sub>3</sub>S: m/z 209.02719.

Photolysis of 1 in p-Xylene. A solution containing 200 mg of 1 in 220 cm³ of p-xylene was irradiated under argon through a Pyrex filter sleeve for 18 h. After evaporation of the solvent, the photolysate was subjected to the chromatography on silica gel using a hexane-ether mixture as the eluent to give 4,4′-dimethylbibenzyl (78 mg, 77%) and 7 (150 mg, 75%). The structure of 4,4′-dimethylbibenzyl was verified by comparison with an authentic sample.

Photolysis of 1 in 2-Propanol. A solution containing 200 mg of 1 in 220 cm³ of 2-propanol was irradiated under argon through a Pyrex filter sleeve for 16 h. After removal of the solvent, the photolysate was subjected to the chromatography on silica gel using a hexane-ether as the eluent to give pinacol (41 mg, 72%) and 7 (157 mg, 78%).

Photolysis of 2 in Benzene. A solution containing of 200 mg of 2 in 220 cm³ of benzene was irradiated under argon through a Pyrex filter for 2 h. Removal of the solvent under reduced pressure left a dark oil which was purified by thick-layer (preparative thin layer) chromatography using a 1:1 mixture of dichloromethane-benzene as the eluent. 11 (9.7 mg, 9%)<sup>7)</sup> was isolated with 93 mg of unreacted starting material. The structure of 11 was identified by comparison with an authentic sample.<sup>8)</sup>

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